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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/603,852	06/25/2003	Kenneth C. Wu	ASC-022CPCN	3708
51414	7590 03/02/2006		EXAMINER	
GOODWIN PROCTER LLP PATENT ADMINISTRATOR		OWENS, DOUGLAS W		
EXCHANGE PLACE			ART UNIT	PAPER NUMBER
BOSTON, MA 02109-2881			2811	

DATE MAILED: 03/02/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)	7		
Office Action Summary		10/603,852	WU ET AL.			
		Examiner	Art Unit	1		
		Douglas W. Owens	2811			
Period fo	The MAILING DATE of this communication apor Reply	ppears on the cover sheet with the	correspondence address			
THE - Exte after - If the - If NO - Failt Any	MAILING DATE OF THIS COMMUNICATION PAILING DATE OF THIS COMMUNICATION PRISONS of time may be available under the provisions of 37 CFR 1 of SIX (6) MONTHS from the mailing date of this communication. The period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period ure to reply within the set or extended period for reply will, by staturely received by the Office later than three months after the mailing patent term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however, may a reply be tiply within the statutory minimum of thirty (30) dad will apply and will expire SIX (6) MONTHS from the, cause the application to become ABANDON	mely filed ys will be considered timely. n the mailing date of this communication. ED (35 U.S.C. § 133).			
Status						
1)🖂	Responsive to communication(s) filed on 121	December 2005.				
2a)⊠	This action is FINAL. 2b) This action is non-final.					
3)	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposit	ion of Claims					
5)⊠ 6)⊠ 7)⊠	Claim(s) <u>See Continuation Sheet</u> is/are pend 4a) Of the above claim(s) is/are withdra Claim(s) <u>See Continuation Sheet</u> is/are allow Claim(s) <u>126-128,179 and 180</u> is/are rejected Claim(s) <u>242-244</u> is/are objected to. Claim(s) are subject to restriction and/	awn from consideration. red. d.				
Applicat	ion Papers					
	9) The specification is objected to by the Examiner.					
10)	10) ☐ The drawing(s) filed on is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.					
	Applicant may not request that any objection to the					
11)	Replacement drawing sheet(s) including the corre The oath or declaration is objected to by the E					
Priority (	under 35 U.S.C. § 119					
a)	Acknowledgment is made of a claim for foreign All b) Some * c) None of:  1. Certified copies of the priority documents. Certified copies of the priority documents. Copies of the certified copies of the prince application from the International Bures. See the attached detailed Office action for a list	nts have been received. nts have been received in Applica fority documents have been receiv au (PCT Rule 17.2(a)).	tion No ved in this National Stage			
Attachmer	• •	۵۰ <del>۱۱ استان می داد</del>	(PTO 442)			
2) Notice 3) Information	ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-948) rmation Disclosure Statement(s) (PTO-1449 or PTO/SB/06 er No(s)/Mail Date 12/12/05.	4) Interview Summar Paper No(s)/Mail [  8) 5) Notice of Informal 6) Other:				

Continuation of Disposition of Claims: Claims pending in the application are 126-129,133,134,140-143,159-170,177-182,188-197,200,204,208-235,239 and 242-244.

Continuation of Disposition of Claims: Claims allowed are 129,133,134,140-143,159-170,177,178,181,182,188-197,200,204,208-232,234,235 and 239.

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#### **DETAILED ACTION**

## Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

2. Claims 126 – 128, 179 and 178 are rejected under 35 U.S.C. 102(e) as being anticipated by US Patent No. 5,963,817 to Chu et al.

Regarding claims 126 – 128 Chu et al. teach a semiconductor structure (Figs. 2 and 3, for example) comprising:

a layer structure comprising an etch-stop layer (29) and having a doping level below 10<sup>18</sup> atoms/cm<sup>3</sup> (it is not doped) and a substantially relaxed layer (16) comprising Si<sub>1-x</sub>Ge<sub>x</sub>; and

wherein the relaxed layer is graded and x<0.2 (Col. 2, lines 22-40).

Regarding claims 179 and 180, Chu et al. teach a method form forming a semiconductor substrate, the method comprising:

providing a first substrate (14); and

forming a layer structure over the first substrate by:

forming a substantially relaxed graded layer comprising Si<sub>1-x</sub>Ge<sub>x</sub> (16) over the substrate; and

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forming a uniform etch-stop layer (29) over the graded layer, the uniform etch-stop layer having a doping level below 10<sup>18</sup> atoms/cm<sup>3</sup>.

## Allowable Subject Matter

- 3. Claims 129, 133, 134, 140 143, 159 170, 177 182, 188 197, 200, 204, 208 235 and 239 are allowed.
- 4. Claims 242 244 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

### Response to Arguments

5. Applicant's arguments filed December 12, 2005 have been fully considered but they are not persuasive.

Applicant argues that Chu et al. do not teach an etch-stop layer comprising a semiconductor material. This feature can be seen in Figs. 1 and 2, where the Si<sub>3</sub>N<sub>4</sub> etch-stop layer comprises Silicon, which is a semiconductor material.

#### Conclusion

6. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any

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extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Douglas W. Owens whose telephone number is 571-272-1662. The examiner can normally be reached on Monday-Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Eddie C. Lee can be reached on 571-272-1732. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Douglas W Owens

Examiner Art Unit 2811

Dørgla K. Owen